

-	39	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (treat\$3 treatment)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:34
-	9436	etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:44
-	15672	((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:23
-	0	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) same (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:46
-	4	(etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) same (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:43
-	10866	(plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:52
-	590	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:46
-	334	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) with ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:51
-	5972	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:51

-	9	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 oxide) (plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:51
-	1989	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) with ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:53
-	0	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:54
-	0	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:54
-	7	((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:54
-	20	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) and (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) and ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:00
-	2	(stabiliz\$5 with high with aspect with ratio) same ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:00

-	79	stabiliz\$5 with high with aspect with ratio	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:00
-	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (stabiliz\$5 with high with aspect with ratio)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:04
-	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) same (stabiliz\$5 with high with aspect with ratio)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:05
-	8529	430/311,313,314,316,317.ccls. 438/710.ccls. 216/67.ccls. 134/1.2.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:05
-	616	((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) and (430/311,313,314,316,317.ccls. 438/710.ccls. 216/67.ccls. 134/1.2.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:06
-	152	(chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:17
-	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:09
-	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:09
-	19	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) 430/\$.ccls.) and ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:10
-	56381	(reduc\$5) near (plasma gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:22
-	222	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:22
-	1412666	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
-	34	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5) near (plasma gas))) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:34

-	435139	(polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:35
-	2	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:46
-	6	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) same ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:41
-	88530	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5) near (plasma gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:45
-	299	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:49
-	19	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5) near (plasma gas)) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:46
-	160	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((reduc\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:49
-	10	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((reduc\$5) near (plasma gas)) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:49
-	11	((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.	USPAT; US-PGPUB	2004/03/02 15:57
-	12	((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.	USPAT; US-PGPUB	2004/03/02 15:54
-	4	ep-903777-\$.did. jp-2000200832-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:57

-	20	(ep-903777-\$.did. jp-2000200832-\$.did.) (((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:57
-	10	((ep-903777-\$.did. jp-2000200832-\$.did.) (((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) and (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) (stabiliz\$5 with high with aspect with ratio))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:06
-	10	((ep-903777-\$.did. jp-2000200832-\$.did.) (((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) not (((ep-903777-\$.did. jp-2000200832-\$.did.) (((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) and (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) (stabiliz\$5 with high with aspect with ratio)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:27
-	2	("6114259").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:27
-	36510	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
-	2545	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:38

-	5376123	(reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
-	1412666	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
-	357	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) (h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:08
-	30	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) with (h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:44
-	31	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) (h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:05
-	28	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) (h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) not (((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) with (h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:06

52	<p>(((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))) and (430/\$.ccls. 438/\$.ccls.)</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p>	<p>2004/03/02 17:08</p>
33	<p>(((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))) and (430/\$.ccls. 438/\$.ccls.) not (((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) not (((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))))) (((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))))))</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p>	<p>2004/03/02 17:09</p>